

Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

OCT 29 2003

(Use as many rows as necessary)

Docket Number (Sequence)

TSMC-01-1388

Application Number

10/628,914

Applicant

Chih-Ming Ke et al.

Filing Date

07/29/03

Priority Art Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
we	611468	19/5/00	Komatsu	250	201.3	6/4/98
we	591671	6/29/99	Butsch et al.	430	30	3/13/97
we	6130432	10/10/00	Pfeiffer et al.	250	396ML	4/13/99
we	5025165	6/18/91	Chen et al.	250	491.1	3/26/90
we	6066849	5/23/00	Masnaghetti et al.	250	310	9/8/98

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)

we	"193nm resist shrinkage", by Su et al., Solid State Technology, May 2001, pp. 52-54 and 57.
we	U.S. Patent Application Serial No. 10/047,266, Filed 1/14/02, "Reducing Photoresist Shrinkage via Plasma Treatment", assigned to the same assignee.
we	

EXAMINER

ZIA R. HASHMI

DATE CONSIDERED

6/29/04

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.